

ETCHING COMPOSITION FOR LAMINATED FILM INCLUDING REFLECTIVE ELECTRODE AND METHOD FOR FORMING LAMINATED WIRING STRUCTURE

ABSTRACT OF THE DISCLOSURE

The etching composition of the invention is capable of simultaneously etching the films of a three-layered laminate film comprising an uppermost amorphous transparent electrode film made of IZO, etc., an intermediate
5 reflective electrode film made of Al, etc. and a lowermost galvanic corrosion-inhibiting film made of Mo, etc. or a two-layered laminate film comprising an upper amorphous transparent electrode film and a lower reflective electrode film by a sole use thereof in a single etching operation to provide an etched laminate film having an edge of a good normal-tapered or
10 stepwise shape. The etching composition comprises an aqueous water containing 30 to 40% by weight of phosphoric acid, 15 to 35% by weight of nitric acid, an organic acid and a cation-generating component.

Figure 1